

# Significant Luminescence Enhancement of Ga-Doped WS<sub>2</sub> Monolayers Grown by CVD

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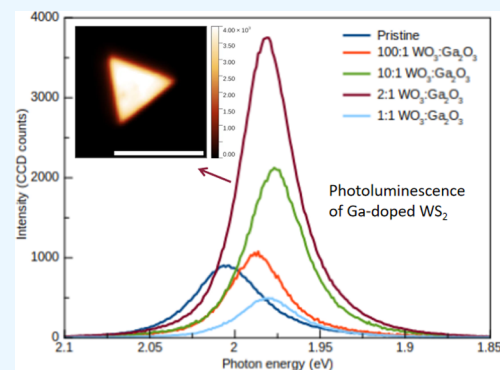
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**ABSTRACT:** Monolayer tungsten disulfide (WS<sub>2</sub>) is a direct-band-gap semiconductor that has excellent luminescence properties, which are of great interest for optoelectronic applications. In this study, we investigated the effect of gallium (Ga) on WS<sub>2</sub> monolayers grown by chemical vapor deposition. Our results indicate that Ga-doped WS<sub>2</sub> exhibits a 3.6-fold increase in photoluminescence intensity for doped samples compared to pristine WS<sub>2</sub>. To confirm the existence of Ga in the WS<sub>2</sub> structures, resonance Raman spectroscopy and X-ray photoelectron spectroscopy (XPS) were utilized as characterization methods. A redshift of the XPS spectrum was observed as well as an increase in the disorder-related Raman modes, which were attributed to the influence of Ga. XPS analysis and ab initio electronic structure calculations reveal the presence of substitutional Ga atoms as well as Ga atoms adsorbed on WS<sub>2</sub> surfaces.



## 1. INTRODUCTION

Transition-metal dichalcogenides (TMDs) are a class of 2D materials that have garnered significant interest due to their unique physicochemical and photoelectronic properties.<sup>1–3</sup> This makes them highly promising candidates for photoelectronic applications.<sup>4–9</sup> Single-layer TMDs feature a three-plane structure where the metal (Me) atomic plane is sandwiched by two chalcogen (X) atomic planes via a strong ion–covalent bond, forming an X–Me–X structure.<sup>10</sup> Unlike bulk or multilayer TMDs, many monolayer TMDs possess a direct band gap.<sup>11,12</sup> One such material is single-layer WS<sub>2</sub>, which is becoming increasingly popular due to its appropriate band gap (1.9 eV),<sup>13,14</sup> strong spin–orbit coupling, and high PL quantum yield.<sup>15–17</sup> These properties give rise to the strong luminescence intensity in WS<sub>2</sub> monolayers, which stand out from those of other TMDs. In fact, as previously mentioned, single-layer WS<sub>2</sub> has a significantly higher PL quantum yield, of around 6%, when compared to other 2D materials (which is about 0.1% for MoS<sub>2</sub>, for instance).<sup>17</sup>

By strategically incorporating and controlling impurities or defects within the lattice of WS<sub>2</sub>, one can significantly alter a specific property to improve the performance of devices for a target application, such as photonics or catalysis. Additionally, defects in TMD structures can impact the PL intensity, as well as other physical or chemical factors, such as the adsorption of complex molecules on the basal plane of monolayered crystals,<sup>18</sup> which is paramount in catalysis applications. In WS<sub>2</sub>, defects usually include W vacancies and S vacancies.<sup>19–21</sup> However, defects also provide an opportunity for doping.<sup>22,23</sup> By incorporating different atoms into a semiconductor, it is

possible to tailor its photoelectronic properties by controlling dopants in the material. For instance, carbon, niobium, and tantalum can be incorporated into TMDs to obtain p-type electronic properties.<sup>24–26</sup> In a recent study, gallium-doped MoS<sub>2</sub> monolayers showed 2 orders of magnitude enhancement in their photoluminescence (PL) response.<sup>22</sup> Plasma surface treatment is another efficient way to dope TMDs with atoms. It has been shown that, through cold plasma treatment, nitrogen was incorporated into the lattice and improved the luminescence properties of WS<sub>2</sub> monolayers.<sup>27</sup> An extensive discussion on the potential applications of monolayers WS<sub>2</sub> can be found in a recent review.<sup>28</sup>

Aiming toward application in photonic and electronic devices, a significant effort has been made to synthesize wafer-sized TMD samples, making them compatible with current technology.<sup>29–31</sup> Although good-quality single-crystal WS<sub>2</sub> can be isolated through an exfoliation method, it is unsuitable for high-volume industrial fabrication. Due to the low cost and high yield, chemical vapor deposition (CVD) and atomic layer deposition are considered the most promising growth strategies to obtain high-quality and large-area 2D TMDs and heterostructures since other synthesis methods, such as epitaxial growth or other chemical routes, either lack

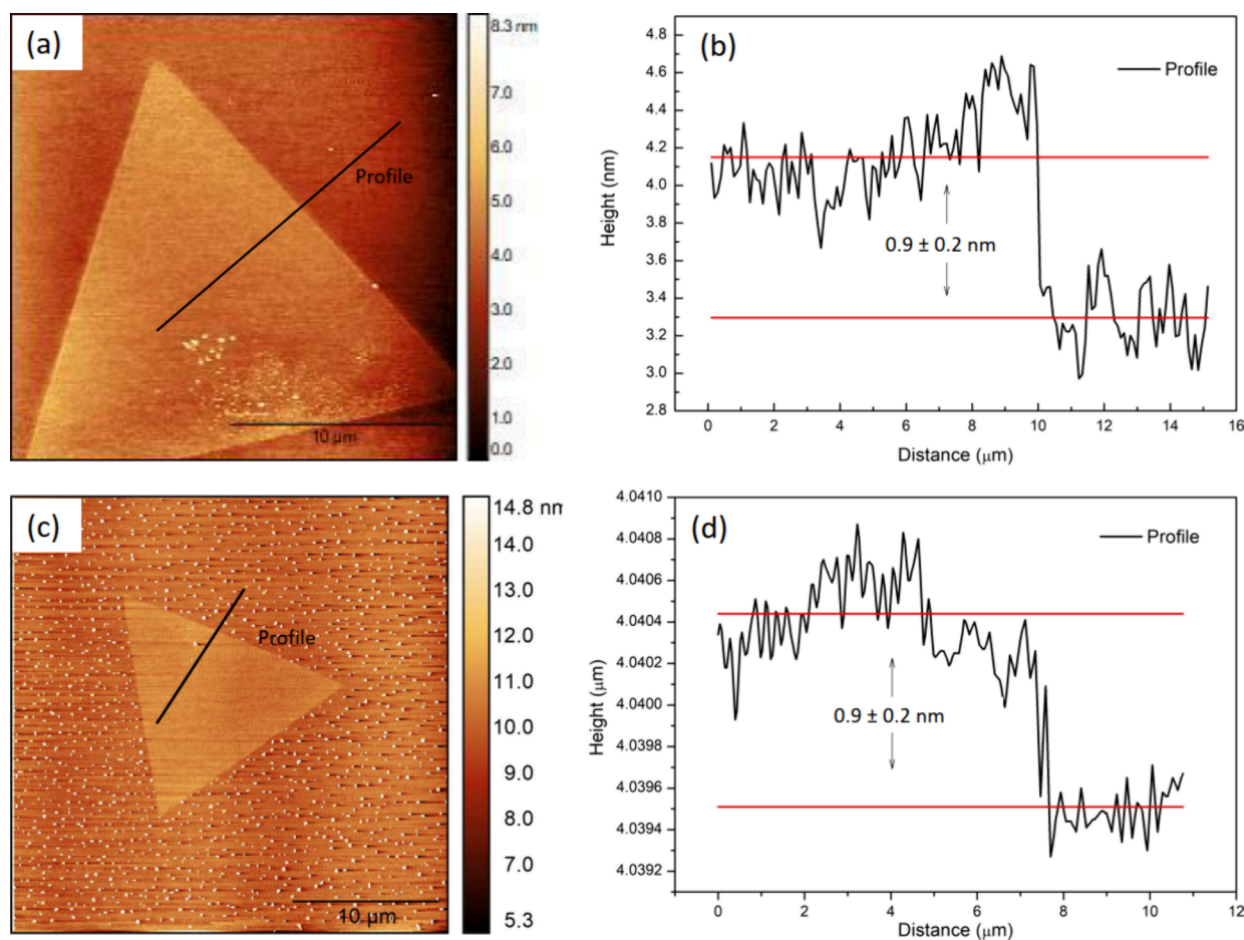
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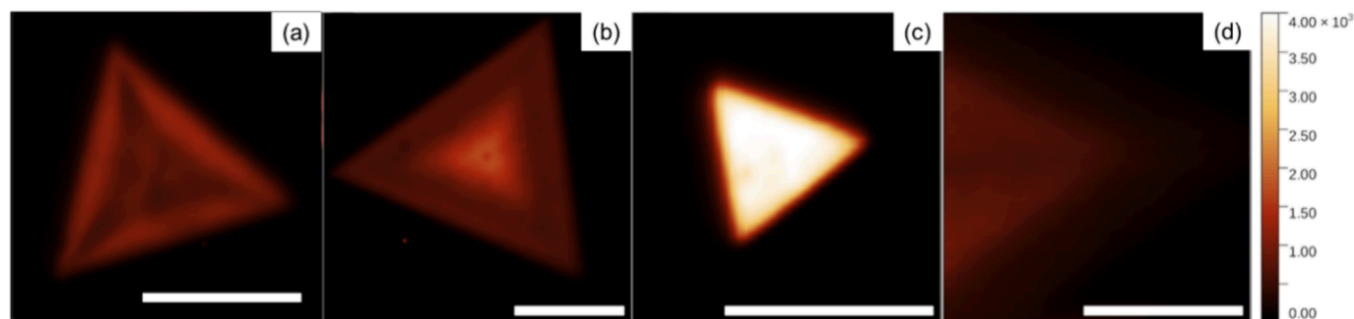
**Figure 1.** (a) and (b) AFM image and height profile of the pristine monolayer WS<sub>2</sub>, whose height is about  $0.9 \pm 0.2$  nm; (c) and (d) AFM image and height profile of the 2:1 Ga-doped WS<sub>2</sub> monolayer, with height  $0.9 \pm 0.2$  nm.

scalability or yield irregular samples.<sup>32–35</sup> CVD allows for efficient TMD growth using a variety of precursor forms, including powders or/and liquids. Sometimes, salt, like NaCl or KBr, is used to generate a transition-metal halide with a reduced melting point, as compared to their transition-metal oxide counterparts, and generate a vapor pressure necessary for deposition to occur on the target substrate. To substitutionally dope TMDs with transition metals, the dopant precursor is either directly mixed with the host transition-metal precursors, placed upstream, or placed onto the target substrate. The approximate dopant concentration is determined by the ratio of the host and the dopant metal precursor. Using this technique, elements from group V (vanadium, niobium, tantalum), rhenium, iron, tin, and lanthanides such as cerium, erbium, and ytterbium have been substitutionally doped in TMDs.<sup>28</sup> However, when it comes to doped TMDs, they are typically produced by creating defects in the crystalline structure, which can weaken the final properties. For that reason, it is essential to develop, or improve, an in situ doping method that can avoid structural damage while effectively introducing dopants into TMDs.

The in situ doping strategy has many advantages over other impurity incorporation strategies since it is a one-step process rather than a multiple-step process. Also, the preparation of the precursors is rather simple, independent of a dry, powder-based mix method<sup>36</sup> or wet-method-based CVD processes. Other surface treatment techniques that are employed, such as

ion bombardment, plasma treatment, or dip-coating, also require further steps in the preparation of the samples.<sup>37–39</sup> These methods require further steps that hinder the final yield and scalability of the CVD process and the implementation of TMD-based devices in the industry. In situ-based growth was employed in previous works by some of the authors, as well as other research groups targeting the modification of different properties, such as the magnetic response of vanadium-doped WSe<sub>2</sub>,<sup>40</sup> as well as luminescence properties in V-WSe<sub>2</sub> monolayers.<sup>41</sup>

This study introduces an in situ CVD approach for synthesizing WS<sub>2</sub> while simultaneously doping it with gallium (Ga) atoms. The inspiration for doping WS<sub>2</sub> with Ga arises from the research conducted by B. Liu and colleagues, where they notably improved the PL intensity of MoS<sub>2</sub> through Ga doping.<sup>22</sup> The Ga-doped samples were synthesized by mixing WO<sub>3</sub> and Ga<sub>2</sub>O<sub>3</sub> powders in different mass ratios ( $m(\text{WO}_3):m(\text{Ga}_2\text{O}_3)$  of 100:1, 10:1, 2:1, and 1:1), and their PL intensities were compared with that of pristine WS<sub>2</sub> monolayers. The PL intensity shows a dependence on the precursors' mass ratio. When the amount of Ga dopant increases from a mass ratio of 100:1 to 1:1, the PL intensity initially increases, reaching a maximum at a mass ratio of 2:1, i.e., up to 3.6 times the PL intensity of pristine samples. It was followed by a decrease for Ga-richer precursor mixtures. In the case of the ratio 1:1, the PL intensity is weaker than that observed for pristine samples. The adsorption of Ga atoms in



**Figure 2.** (a–d) PL maps of pristine, 100:1, 2:1, and 1:1  $\text{WO}_3:\text{Ga}_2\text{O}_3$  mass ratios, respectively. One may observe the intensity gain and uniformity of the 2:1 Ga-doped samples. The scale bar in all of the figures is  $10\ \mu\text{m}$ .

substitutional W sites has been revealed by X-ray photoelectron spectroscopy (XPS) measurements and confirmed by ab initio calculations.

## 2. SYNTHESIS, CHARACTERIZATION, AND THEORETICAL PROCEDURES

The synthesis process followed a similar protocol developed in ref 37. The details of the growth process can be found in the Supporting Information (SM).  $\text{WS}_2$  was prepared by CVD. Sulfur (S) and tungsten trioxide ( $\text{WO}_3$ ) were used as precursors for the preparation of  $\text{WS}_2$ , while doped  $\text{WS}_2$  mixtures of  $\text{WO}_3$  and gallium trioxide ( $\text{Ga}_2\text{O}_3$ ) were used with different mass ratios. In this study, the mass ratios of the mixture were  $m(\text{WO}_3):m(\text{Ga}_2\text{O}_3) = 100:1, 10:1, 2:1, \text{ and } 1:1$ . 20 mg of  $\text{WS}_2$  powder or powder mixed with  $\text{Ga}_2\text{O}_3$  was put in a crucible. A  $\text{SiO}_2$  (275 nm thick)/Si wafer was placed diagonally above the powder, with one edge of the wafer placed at the bottom of the crucible and the opposite edge placed on the inside wall of the crucible (see the SM). In addition, 300 mg of sulfur powder was positioned in another crucible. The amount of S was the same for the growth of the pristine and doped samples. The two crucibles were placed into a quartz tube, and it was placed in a two-stage furnace.  $\text{WS}_2$  monolayers were synthesized on the  $\text{SiO}_2$  surface. The experimental scheme and the temperature curve profile are shown in Figure S1.

Atomic force microscopy (AFM), Raman, and PL measurements were performed by using the same instrument (NT-MDT NTEGRA SPECTRA), equipped with a solid-state 532 nm laser. The diameter of the focused laser spot is about 1 micrometer, and its power ranges from 0.02 to 2 mW, controlled by a variable neutral density filter. The focal length of the spectrometer is 52 cm. Raman spectra were taken using an 1800 L/mm grating, yielding a resolution of  $0.8\ \text{cm}^{-1}$ . PL maps were performed using a 150 L/mm grating, yielding a 4 meV resolution. The PL map intensity data reported in the text are related to the average data acquired from several maps performed in different samples to ascertain the reproducibility of the results. Also, the  $2\text{LA}(M)+E_{2g}$  mode was used as a normalizing parameter for the PL peaks and maintained at a fixed value ( $\sim 100$  counts) during the measurements.

The surface analysis chamber is equipped with a SPECS PHOIBOS 100/150 hemispherical analyzer. XPS measurements were conducted at a pressure of  $1.2 \times 10^{-9}$  Torr, and the  $\text{Al-K}\alpha$  X-ray line was used. During measurement, the analyzer was positioned at a  $90^\circ$  angle to the sample surface normal. XPS data analysis was performed using CasaXPS software. The C1s peak was used for XPS data energy

calibration. The measured C–C peak position was set to 284.6 eV, and this calibration was used for all data from the same sample. The XPS line was deconvolved using pseudo-Voigt line shapes, and the Shirley background was used as the baseline.

Density functional theory (DFT) calculations were performed using the VASP code.<sup>37</sup> For the exchange–correlation functional, the Perdew–Burke–Ernzerhof generalized gradient approximation was used, including Tkatchenko–Scheffler dispersion corrections.<sup>38</sup> Periodic boundary conditions with  $4 \times 4 \times 1$  and  $5 \times 5 \times 1$  supercells were considered. A cutoff energy of 500 eV and a  $3 \times 3 \times 1$  grid of  $k$ -points were used. The formation energies ( $E_f$ ) were calculated using the approach described in ref 39.

## 3. RESULTS AND DISCUSSIONS

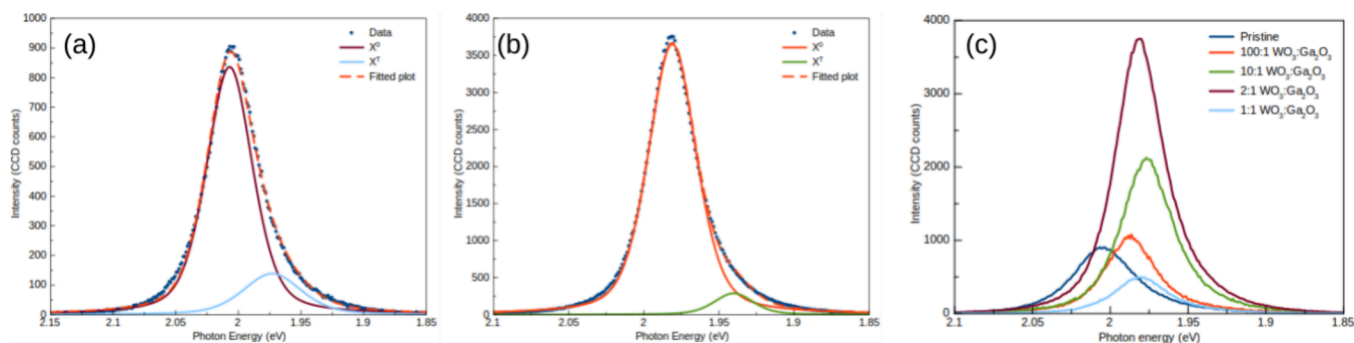
AFM measurements were performed in the semicontact mode to directly measure the height of the monolayer structures. The micrographs and height profiles are shown in Figure 1. The height profiles measured for the pristine and doped samples were  $0.8 \pm 0.2$  and  $0.9 \pm 0.2$  nm, which are within the expected values found in ref 40.

Figure 2a–d shows the PL maps of pristine and Ga-doped monolayered samples grown with different W and Ga oxide precursor ratios. The presence of Ga in the growth process did not change the growth dynamics, and the monolayered morphology yielded predominantly triangular structures, as shown in Figure S2. It is also shown, in Figure S4, that the overall peak shift was observed for different monolayer structures, correlating with the data in Table 1. The triangular

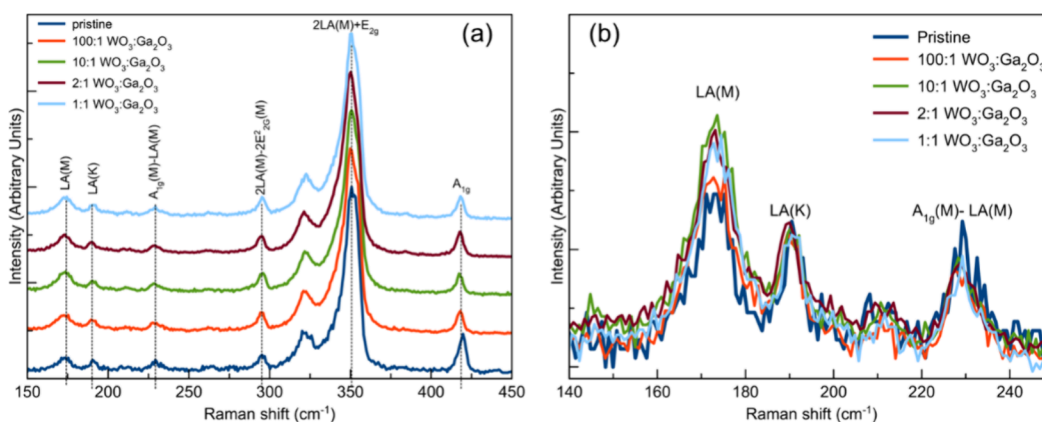
**Table 1.** PL Peak Parameters as a Function of the  $\text{WO}_3:\text{Ga}_2\text{O}_3$  Mass Ratio

	pristine	100:1	10:1	2:1	1:1
$X^0$ pos (eV)	2.01	1.988	1.977	1.981	1.981
$X^T$ pos (eV)	1.970	1.944	1.939	1.940	1.940
$X^0/X^T$ ratio	6.1	14.6	13.9	12.7	15.1
line shape shift (meV)		19	30	26	26

monolayers doped with Ga showed a more uniform luminescence behavior compared to the pristine ones. The strongest luminescence signal was observed in structures synthesized using a 2:1  $m(\text{WO}_3):m(\text{Ga}_2\text{O}_3)$  mass ratio. The PL intensity was uniform and, on average, 3.6 times more intense for these doped samples compared with the pristine ones, as is clear from Figures 2c and 3c, as well as from Figure S5 in the Supporting Information. The average intensities were obtained by averaging the mean intensity obtained from the PL



**Figure 3.** (a, b) PL peak deconvolution showing the  $X^0$  and  $X^T$  contributions for the pristine and  $m(\text{WO}_3):m(\text{Ga}_2\text{O}_3) = 2:1$  samples, respectively. The smaller contribution of  $X^T$  to the line shape of the emission suggests that the adsorption of gallium enhances the direct recombination process, which directly affects the overall intensity of the PL peak. Panel (c) shows the average PL obtained from samples grown using different mass ratios of  $\text{WO}_3$  and  $\text{Ga}_2\text{O}_3$ . There is a displacement of the PL peak due to the adsorption of Ga. The redshift PL observed for the  $m(\text{WO}_3):m(\text{Ga}_2\text{O}_3) = 2:1$  ratio sample is 26 meV.



**Figure 4.** (a) Raman spectra of pristine and Ga-doped samples synthesized with different mass ratios. It is possible to observe a shift in the  $A_{1g}$  peak of around  $0.7 \text{ cm}^{-1}$  for all doped samples. (b) Lower-frequency spectral region. The  $LA(M)$  vibrational mode ( $176 \text{ cm}^{-1}$ ) increases due to increasing disorder effects in the samples, a behavior not followed by the  $LA(K)$  ( $190 \text{ cm}^{-1}$ ) and  $A_{1g}(M)-LA(M)$  ( $224 \text{ cm}^{-1}$ ) vibrational modes. The excitation wavelength was 532 nm.

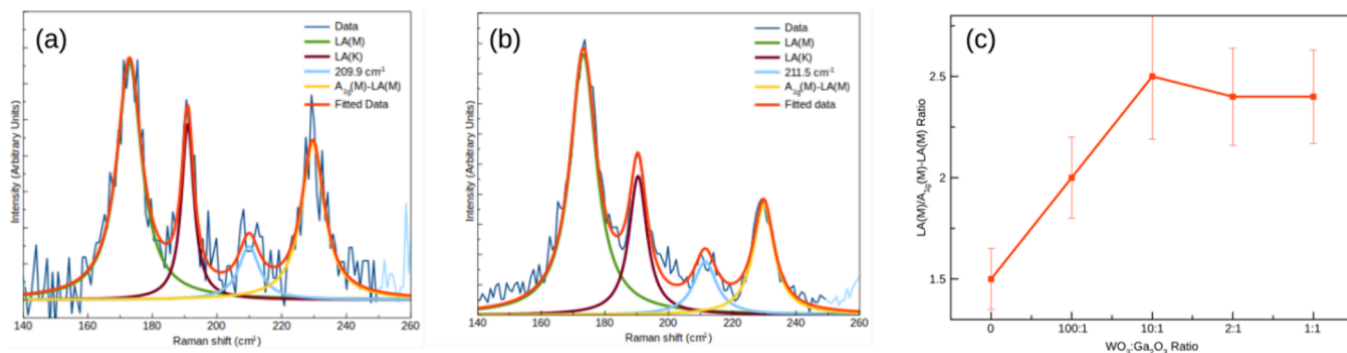
maps of several monolayer crystals. It is important to note that the results are an adequate average of several points from different triangles instead of an isolated peak intensity value inside the monolayer triangle. The more intense emission from the edges of pristine samples in Figure 2a is well discussed in the literature.<sup>41</sup> This phenomenon is due to the high density of S vacancies in the basal plane of  $\text{WS}_2$  monolayers with respect to the edge, where excitonic recombination is more probable.

In Figure 3a,b, the PL peaks are representative of the averaged emission of the structures for the pristine sample and the sample prepared with a mass ratio of  $\text{WO}_3:\text{Ga}_2\text{O}_3 = 2:1$ , respectively. We can correlate the average intensity with the precursor powder mixtures, as shown in Figure S5. Figure 3c shows the PL spectra of samples prepared with different mass ratios as well as the PL spectrum obtained from a pristine sample. As is clear from this figure, the presence of Ga also affected the emission energy of the doped samples. It was possible to see a shift of the emission peak up to  $\sim 26 \text{ meV}$  upon an increase of Ga in the precursor mixture (Table 1). It is well-known that CVD-grown TMDs are naturally n-doped due to the presence of S vacancies. The observed shift shows that the presence of Ga in the structure dopes the material by changing its emission due to the creation of defect states in the band gap. This is compatible with the process of substitutional doping and may also be responsible for increasing the  $X^0$  exciton line contribution and intensity,<sup>42</sup> as well as increasing

the  $X^0/X^T$  ratio as shown in Table 1. These changes suggested that Ga atoms are passivating sulfur vacancies, as the density of S vacancies contributes to PL processes via the trion emission. That is, the trion contribution to the line shape is lower for the doped samples, as shown in Figure 3. At low Ga concentrations, sulfur passivation does not immediately contribute to nonradiative processes; however, for highly doped samples, the incorporation of Ga introduces new defect states, increasing the concentration of sites where nonradiative recombination processes may take place. This is a recombination pair that enhances the Auger recombination process,<sup>43</sup> which is not related to trions or neutral excitons. This effect may be due to the strong alloying of the monolayer structures or an effect of strain due to augmented lattice deformation in the presence of Ga impurities.

A recent report revealed an enhancement of PL intensities seen from the fluorescent spectra of Er-doped  $\text{WS}_2$  monolayers compared with those of the pristine samples. In this case, Er atoms are substitutional in W sites.<sup>44</sup> In the case of Nb p-doped  $\text{WS}_2$  grown by CVD, Nb atoms also substituted the W atom in the  $\text{WS}_2$  lattice but quenched the PL emission.<sup>45</sup>

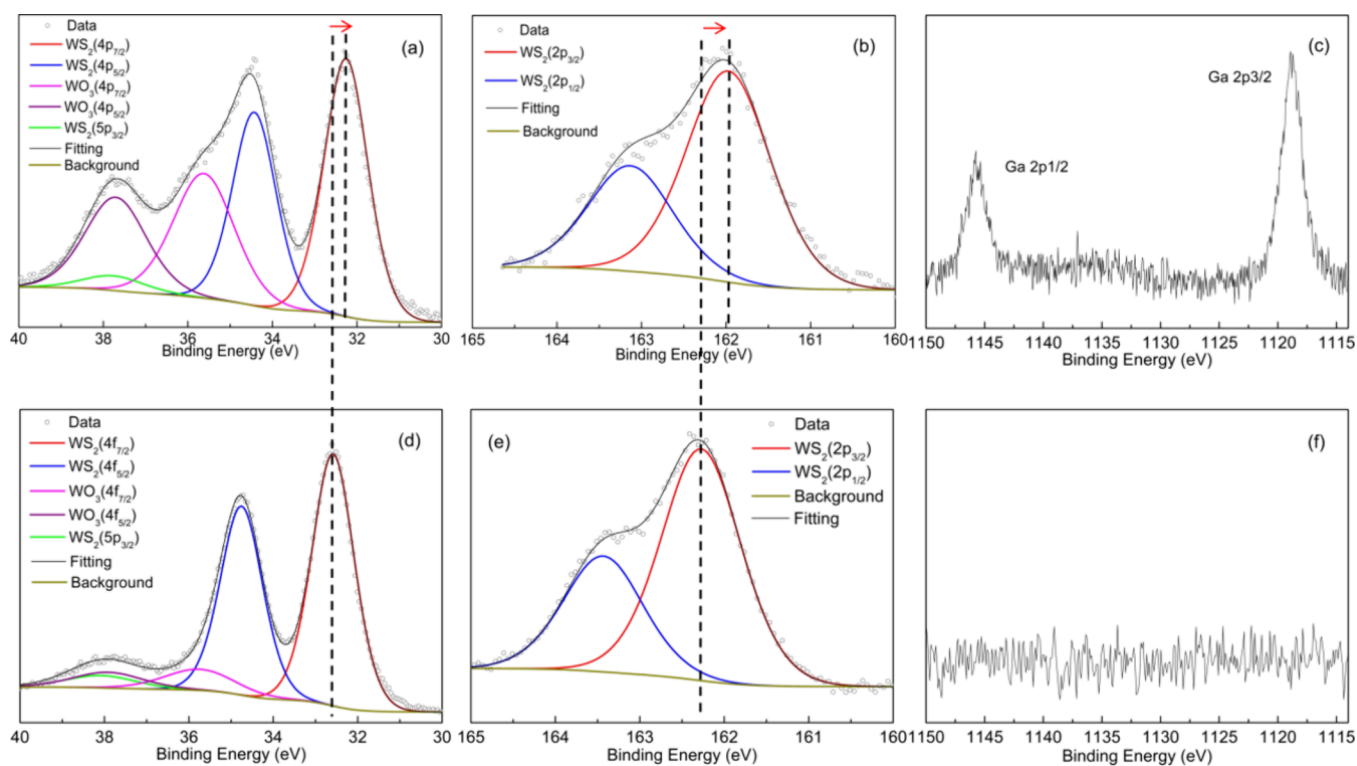
Figure 4a shows the full-range Raman spectra of pristine and Ga-doped  $\text{WS}_2$  monolayers. Raman spectra of the  $\text{WS}_2$  crystal show two main peak contributions: the in-plane  $2LA(M)+E_{2g}$  mode at  $\sim 355 \text{ cm}^{-1}$  and the out-of-plane  $A_{1g}$  mode at  $\sim 419 \text{ cm}^{-1}$ . Indeed, the second-order  $2LA(M)$  convolved with the



**Figure 5.** (a) Lower-frequency Raman spectrum from the pristine WS<sub>2</sub> monolayer sample. (b) Same spectral region, in this case for the 2:1 Ga-doped sample (the WO<sub>3</sub>:Ga<sub>2</sub>O<sub>3</sub> mass ratio is 2:1). (c) Evolution of [LA(M)/(A<sub>1g</sub>(M)-LA(M))] as a function of the WO<sub>3</sub>:Ga<sub>2</sub>O<sub>3</sub> mass ratio. The excitation wavelength was 532 nm.

**Table 2.** Position Parameters and Peak Ratio of the Pristine and Ga-Doped Samples

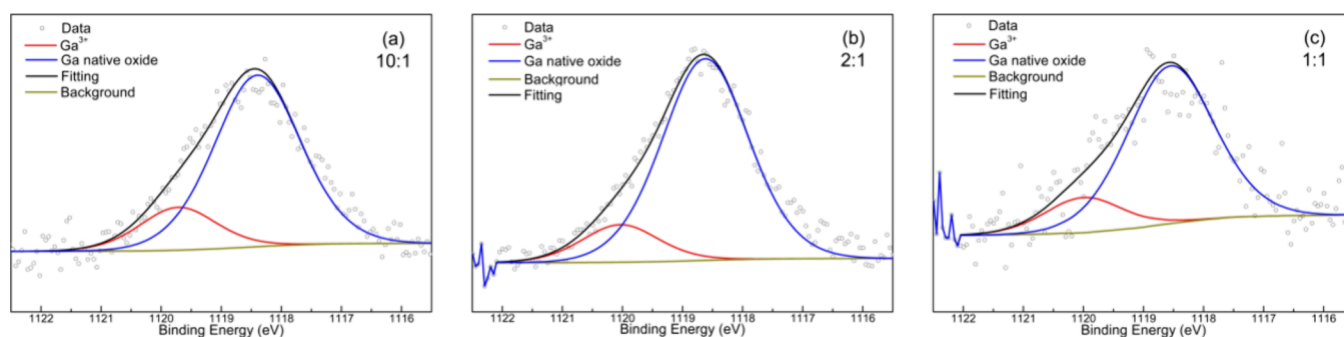
	pristine	100:1	10:1	2:1	1:1
LA(M) pos (cm <sup>-1</sup> )	172.8	173.44	173.9	173.2	173.2
LA(K) pos (cm <sup>-1</sup> )	190.9	191.33	191.7	190.4	191.1
A <sub>1g</sub> (M)-LA(M) pos (cm <sup>-1</sup> )	229.7	230.2	230.1	229.9	229.4
LA(M):[A <sub>1g</sub> (M)-LA(M)] ratio	1.5	2.0	2.6	2.4	2.4



**Figure 6.** (a–c) XPS spectra of W4f, S2p, and Ga2p of Ga-doped WS<sub>2</sub> samples prepared with a 2:1 WO<sub>3</sub>:Ga<sub>2</sub>O<sub>3</sub> mass ratio; (d–f) spectra of W4f, S2p, and Ga2p of pristine WS<sub>2</sub> samples. There is a clear shift toward lower binding energies for the Ga-doped WS<sub>2</sub> sample, as is shown by the dashed line and arrow in the figure.

E<sub>2g</sub> mode is the most intense feature of the spectra. It is expected that the A<sub>1g</sub> mode is sensitive to doping effects.<sup>46</sup> A small shift toward lower frequencies and softening of the A<sub>1g</sub> mode were seen in the Ga-doped samples, as shown in Figure 4a; also, off-resonance measurements did not show a peak shift in the E<sub>2g</sub> mode, indicating the samples were not affected by strain effects due to Ga incorporation (Figure S6). This minor change may be mostly due to out-of-plane vibrations affected

by the presence of Ga impurities in the basal plane of the crystal interacting with the top S layer. The A<sub>1g</sub> redshift is not an effect of induced heat or damage during the measurements because the reproducibility of the spectra was tested at different laser powers without any change, or any effect of strain, which would strongly affect the line shape in the 2LA(M) spectral region due to the splitting of the E<sub>2g</sub> mode in the two contributions. Hence, the Raman spectra evidence the



**Figure 7.** Deconvoluted Ga $2p_{3/2}$  XPS spectra of doped samples prepared with different WO $_3$ :Ga $_2$ O $_3$  mass ratios of 10:1 (a), 2:1 (b), and 1:1 (c).

presence of Ga in the lattice as well as indicate a p-type doping effect,<sup>47,48</sup> which is also confirmed by the energy shift in the position of the valence band maximum (VBM), shown in Figure S10.

However, at an excitation wavelength of 532 nm, one can observe more features due to the resonance Raman effect. This effect is due to the excitation laser energy resonance with the X<sup>b</sup> exciton of WS $_2$ , which shows an absorption peak at around 520 nm ( $\sim 2.4$  eV).<sup>49</sup> Specifically, disorder-related modes in the lower-frequency part of the spectrum were seen.<sup>50</sup> They may be used to infer the influence of the presence of impurities in the lattice, as is the case of the heteroatoms, or as the change of the density of defects in the material compared to the pristine samples.<sup>48</sup> It is shown in Figure 4b that the intensity of the LA(M) vibrational mode at 176 cm<sup>-1</sup> increases upon the increase of the Ga $_2$ O $_3$  concentration in the precursor mixture.

In Figure 5a,b, we present the low-frequency Raman spectra obtained from a pristine sample and a monolayer prepared with an  $m(\text{WO}_3):m(\text{Ga}_2\text{O}_3)$  mass ratio of 2:1, respectively. Further, the LA(M)/[A $_{1g}$ (M)-LA(M)] intensity ratio increases from 1.5 to 2.4, as shown in Figure 5c. The error in this ratio is around 10%. This ratio is of the most importance to qualitatively verify the increase in the density of defects in the treated samples as the A $_{1g}$ (M)-LA(M) combined mode intensity remains nearly constant across all samples. Considering that heteroatoms induce disorder effects, this result also suggests the presence of Ga atoms in the crystal lattice.

As seen in Table 2, where we list the position of the main features of the low-frequency Raman spectrum, an overall spectral shift, if any, was not observed, and any conclusion based on a position change of the peaks cannot be made, despite the increase of the density of defects as a result of the presence of Ga atoms in the lattice structure, as suggested in Figure 5c.

To ascertain the presence of Ga atoms in WS $_2$  monolayers, XPS was employed for analysis. The XPS spectra of Ga-doped WS $_2$  and pristine WS $_2$  are presented in Figure 6. Specifically, Figure 6a–c illustrates the W4f, S2p, and Ga2p regions of the Ga-doped sample prepared with a 2:1 WO $_3$ :Ga $_2$ O $_3$  mass ratio as the precursor. In contrast, Figure 6d,e displays the W4f, S2p, and Ga2p regions of pristine WS $_2$  samples. Analysis of Figure 6a,b reveals that, in the Ga-doped sample, the W4f and S2p peaks are shifted to lower binding energies by 0.41 and 0.40 eV, respectively, compared to the pristine sample (Figure 6d,e). The redshift of W4f and S2p peaks in the Ga-doped WS $_2$  samples indicates a shift of the Fermi level toward the valence band due to the presence of Ga atoms. From the analysis of the XPS spectra, we were able to determine the ratio between S and W atoms (S/W) as being equal to  $2.10 \pm 0.15$  for pristine

samples and  $1.90 \pm 0.15$  for samples synthesized using as precursor a mixture of oxides with a mass ratio of 2:1. To obtain this (S/W) ratio, only W atoms bonded to S atoms were considered, indicating that both pristine and Ga-WS $_2$  samples were nearly stoichiometric. It is also important to note that there is no shift in the position of the WO $_3$  peaks, showing that the oxide was not incorporated in the samples. The binding energy peaks of Ga $2p_{1/2}$  and Ga $2p_{3/2}$  are distinctly seen in the Ga-doped WS $_2$ , while no meaningful signals are present in the same region for pristine WS $_2$ , as depicted in Figure 6c,f. This observation serves as direct evidence of the presence of Ga in the Ga-WS $_2$  samples.

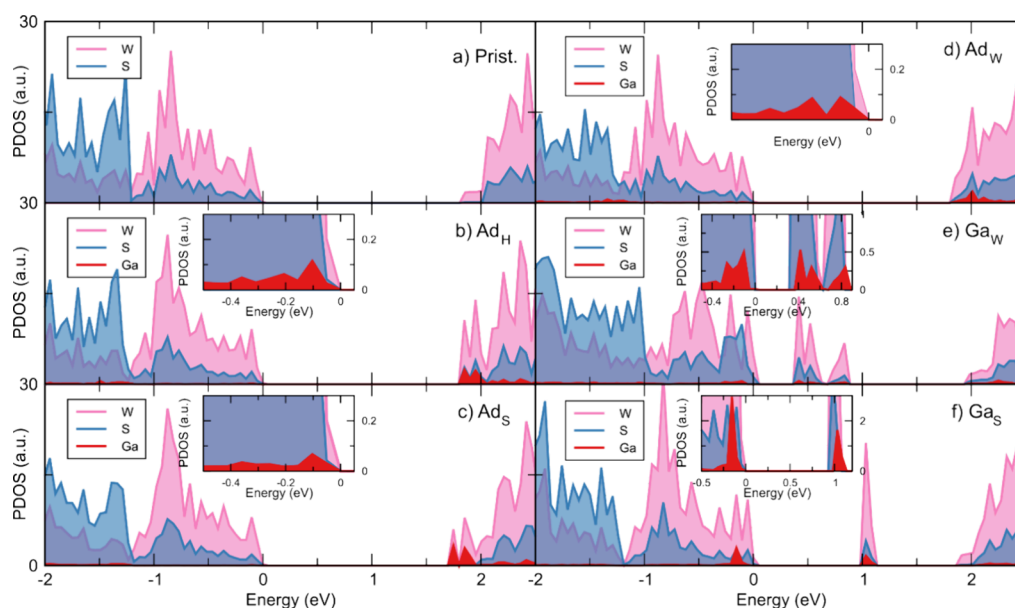
A detailed analysis of the Ga peaks is presented in Figure 7. The content of Ga in the sample prepared with a 100:1  $m(\text{WO}_3):m(\text{Ga}_2\text{O}_3)$  ratio was below the detection limit of our XPS system. For all mass ratios analyzed, the XPS spectra were deconvoluted into two peaks: one at 1120.1 eV (fwhm = 1.75 eV) and the second at 1118.5 eV (fwhm = 1.70 eV), the latter being the dominant one. When the spectra are interpreted, we can rule out the presence of both metallic Ga and Ga $_2$ O $_3$ . This is because the position of the bands corresponding to them would be 1116.7 eV (fwhm = 1.04 eV)<sup>51,52</sup> and 1117.7 eV (fwhm = 1.53 eV),<sup>52,53</sup> respectively. Based on results reported in the literature, we attributed the band at 1118.8 eV to the presence of Ga native oxide and the band at 1120.2 eV to Ga $^{3+}$ .<sup>51,54</sup> These results substantiate the adsorption of Ga into the WS $_2$  structures, thereby influencing the electronic properties.

In Table 3, we present the contents of W, S, and Ga $^{3+}$  as well as the ratio W/S. The amount of Ga $^{3+}$  increases with the

**Table 3. Chemical Composition of the Samples, Considering the Contribution of W and S from Figure 6 and the Ga $^{3+}$  from Figure 7**

	pristine	10:1	2:1	1:1
Ga $^{3+}$ (at %)		0.5	1.3	1.5
W (at %)	32.1	32.9	34	39.1
S (at %)	67.9	66.6	64.7	59.5
S:W ratio	2.1	2	1.9	1.5

increase of Ga in the mixture. In effect, the total amount of Ga increases from 2% up to 10% (not shown in Table 3), and for the case of samples prepared with equal masses of the WO $_3$  and Ga $_2$ O $_3$  ratio, this can explain the observed reduction of PL intensity. In fact, for these oxide masses, the W/S ratio (1.5) is another indication of the loss of quality of the crystal structure and, consequently, the observed reduction in PL.



**Figure 8.** Projected density of states. (a) Pristine WS<sub>2</sub>, (b) Ad<sub>H</sub>, (c) Ad<sub>S</sub>, (d) Ad<sub>W</sub>, (e) Ga<sub>W</sub>, and (f) Ga<sub>S</sub>. Insets show an augmented view of the Ga impurity states near the band edge.

The VBM of both pristine and 2:1 Ga-doped WS<sub>2</sub> samples is presented in Figure S10, determined using the linear extrapolation method. A shift toward lower binding energies indicates that the Fermi level is moving closer to the VBM, suggesting p-type doping as a result of Ga incorporation. This observation is consistent with the Raman spectroscopy results.

To confirm the scenario suggested by the XPS and Raman results, DFT calculations were performed. They were conducted by the Vienna ab initio simulation package (VASP).<sup>37</sup> Information on the computational details can be found in the Supporting Information. The formation energies ( $E_F$ ) were obtained following the procedure of Kieczka et al.<sup>39</sup> as follows:

$$E_F = E_{\text{Sys.}} - \left( E_{\text{Prist.}} + \sum_i n_i \mu_i \right) \quad (1)$$

Here,  $E_F$  is the defect formation energy,  $E_{\text{Sys.}}$  is the energy of the system with the defect,  $E_{\text{Prist.}}$  is the energy of the system without the defect,  $\mu_i$  is the chemical potential, and  $n_i$  is an index that can be +1 or -1 depending on the addition or subtraction of an atom into the lattice, respectively. The systems considered were the Ga atom as a substitutional impurity replacing W (Ga<sub>W</sub>) or S (Ga<sub>S</sub>) and the scenarios where one Ga atom is adsorbed above the W atom (Ad<sub>W</sub>), above the S atom (Ad<sub>S</sub>), or above the hexagonal center (Ad<sub>H</sub>). In the Supporting Information, we describe in detail how the chemical potentials were calculated, and we also present a figure describing the positions of the adsorbed atoms. In the case of adsorbed impurities, the smaller  $E_F$  is 6.10 eV for the Ad<sub>W</sub> system. For the Ad<sub>H</sub> and Ad<sub>S</sub> systems, we obtained  $E_F$  equal to 6.19 and 6.32 eV, respectively. When substitutional impurities are considered,  $E_F$  depends on the W and S chemical potentials. Thus, depending on the experimental conditions, we get different values for  $E_F$ . For S-rich conditions, we obtained  $E_F$  equal to 5.52 and 8.65 eV for Ga<sub>W</sub> and Ga<sub>S</sub>, respectively. On the other hand, for W-rich conditions, we obtained  $E_F$  equal to 8.54 and 7.13 eV for Ga<sub>W</sub> and Ga<sub>S</sub>, respectively. Simulations thus confirm that Ga is likely to be

adsorbed, while it could be substituted depending on the deposition process.

Noteworthy that despite the adsorption cases and the Ga<sub>W</sub>, under S-rich conditions, being the formed configurations, the localized states formed in the latter suggest that the PL can be red-shifted. Likewise, we would like to point out that our simulations show that the adsorption of Ga will interact with the top S layer, which agrees with the shift and softening of the modes of the Raman spectrum.

In Figure 8, the projected density of states of the configurations is shown. Here, we notice that the Ga impurities introduce states in the electronic gap for the Ga<sub>S</sub> and Ga<sub>W</sub> substitutional cases. However, in other cases, it introduces states near the top of the valence band. This agrees with our experimental results of the Ga introducing a p-type degeneration. To support this idea, we show the atomic net charges calculated in Table 4, from the DFT electronic density,

**Table 4.** Atomic Net Charges Calculated from the DFT Electronic Density Using the Bader Approach<sup>45,53</sup>

	Bader net atomic charge		
	W (avg.)	S (avg.)	Ga
Ad <sub>H</sub>	+1.234	-0.634	+0.537
Ad <sub>W</sub>	+1.224	-0.631	+0.605
Ad <sub>S</sub>	+1.225	-0.626	+0.424
Ga <sub>W</sub>	+1.251	-0.622	+1.120
Ga <sub>S</sub>	+1.181	-0.622	+0.393
prist. WS <sub>2</sub>	+1.239	-0.619	

<sup>a</sup>For W and S atoms, the average net charges are presented.

using the Bader approach.<sup>55,56</sup> For pristine WS<sub>2</sub>, as expected, W atoms lose around 1.2 electrons to the surrounding S atoms. In the case of systems with Ga impurities, we present in the table the average of the Bader net charges for the atoms in the supercell. In these cases, we see that the Ga impurities always lose electrons to the WS<sub>2</sub> matrix.

The electron transfer from Ga impurities to WS<sub>2</sub> can be explained by the differences in electronegativity and ionization

potential of W and S with Ga atoms. In Figure S9 of the Supporting Information, the electronegativities and ionization potentials are displayed. Interestingly, in ref 57, Christopoulos et al. calculated the Bader net charges in doped Si, Ge, and Si<sub>1-x</sub>Ge<sub>x</sub>. They show that for typical p-type impurities such as Al, Ga, and In, there is an electron transfer from the impurity to the hosting material.

#### 4. SUMMARY AND CONCLUSIONS

In summary, our work showed that the in situ doping strategy effectively incorporates Ga impurities to WS<sub>2</sub> monolayers, in which its most significant effect is an enhancement of the luminescence intensity of up to 3.6 times when compared to pristine WS<sub>2</sub> with similar triangular morphologies, where the main contribution to the PL line shape arises from the neutral exciton recombination, which is evidence of Ga atoms patching sulfur vacancies. Also, Raman spectroscopy revealed that the presence of Ga affects the crystals' vibrational properties, where disorder-related effects are directly affected and where the LA(M)/[A<sub>1g</sub>(M)-LA(M)] peak intensity ratio increased due to the presence of Ga impurities in the lattice. In particular, the small redshift observed in the A<sub>1g</sub> mode indicates that Ga species are p-doping the WS<sub>2</sub> monolayers, which is compatible with the literature results seen elsewhere. Finally, XPS corroborates this by showing a clear energy redshift in the W<sub>4f</sub> and S<sub>2p</sub> regions. Moreover, the observed evolution in the Ga<sub>2p</sub> region serves as compelling evidence, indicating a correlation of the amount of Ga incorporated into the lattice with respect to the precursor proportion ratio. Both XPS results and DFT calculations agree that Ga is mostly adsorbed on the WS<sub>2</sub> surfaces, while a small percentage of Ga was incorporated into the crystal lattice at the structure on the W sites.

#### ■ ASSOCIATED CONTENT

##### SI Supporting Information

The Supporting Information is available free of charge at <https://pubs.acs.org/doi/10.1021/acsomega.5c01066>.

CVD growth method and conditions; optical microscopy of grown samples; PL spectra of precursors; supplementary PL data; off-resonance Raman spectra; computational details of DFT calculations; and supplementary XPS data (PDF)

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#### Notes

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#### ■ REFERENCES

- (1) Koperski, M.; Molas, M. R.; Arora, A.; Nogajewski, K.; Slobodeniuk, A. O.; Faugeras, C.; et al. Optical properties of atomically thin transition metal dichalcogenides: observations and puzzles. *Nanophotonics* **2017**, *6*, 1289–1308.
- (2) Zhang, X.; Lai, Z.; Ma, Q.; Zhang, H. Novel structured transition metal dichalcogenide nanosheets. *Chem. Soc. Rev.* **2018**, *47*, 3301–3338.
- (3) Zhao, B.; Shen, D.; Zhang, Z.; Lu, P.; Hossain, M.; Li, J.; et al. 2D Metallic Transition-Metal Dichalcogenides: Structures, Synthesis, Properties, and Applications. *Adv. Funct. Mater.* **2021**, *31*, No. 2105132.
- (4) Choi, W.; Choudhary, N.; Han, G. H.; Park, J.; Akinwande, D.; Lee, Y. H. Recent development of two-dimensional transition metal dichalcogenides and their applications. *Mater. Today* **2017**, *20*, 116–130.
- (5) Ahmed, T.; Zha, J.; Lin, K. K.; Kuo, H.; Tan, C.; Lien, D. Bright and Efficient Light-Emitting Devices Based on Two-Dimensional Transition Metal Dichalcogenides. *Adv. Mater.* **2023**, *35*, No. 2208054.
- (6) Kim, K. S.; Kwon, J.; Ryu, H.; Kim, C.; Kim, H.; Lee, E.-K.; et al. The future of two-dimensional semiconductors beyond Moore's law. *Nat. Nanotechnol.* **2024**, *19*, 895–906.
- (7) Withers, F.; Del Pozo-Zamudio, O.; Mishchenko, A.; Rooney, A. P.; Gholinia, A.; Watanabe, K.; et al. Light-emitting diodes by band-structure engineering in van der Waals heterostructures. *Nat. Mater.* **2015**, *14*, 301–306.
- (8) Ottaviano, L.; Mastroppolito, D. The future ahead gas sensing with two-dimensional materials. *Appl. Phys. Lett.* **2023**, *123*, 123.

- (9) Catalán-Gómez, S.; Briones, M.; Cortijo-Campos, S.; García-Mendiola, T.; de Andrés, A.; Garg, S.; et al. Breast cancer biomarker detection through the photoluminescence of epitaxial monolayer MoS<sub>2</sub> flakes. *Sci. Rep.* **2020**, *10*, 10.
- (10) Wilson, J. A.; Yoffe, A. D. The transition metal dichalcogenides discussion and interpretation of the observed optical, electrical and structural properties. *Adv. Phys.* **1969**, *18*, 193–335.
- (11) Mak, K. F.; Lee, C.; Hone, J.; Shan, J.; Heinz, T. F. Atomically Thin MoS<sub>2</sub>: A New Direct-Gap Semiconductor. *Phys. Rev. Lett.* **2010**, *105*, 105.
- (12) Yu, Z. G.; Yakobson, B. I.; Zhang, Y.-W. Realizing Indirect-to-Direct Band Gap Transition in Few-Layer Two-Dimensional MX<sub>2</sub> (M = Mo, W; X = S, Se). *ACS Applied Energy Materials* **2018**, *1*, 4115–4121.
- (13) Kumar, A.; Ahluwalia, P. K. Electronic structure of transition metal dichalcogenides monolayers 1H-MX<sub>2</sub> (M = Mo, W; X = S, Se, Te) from ab-initio theory: new direct band gap semiconductors. *European Physical Journal B* **2012**, *85*.
- (14) Blundo, E.; Felici, M.; Yildirim, T.; Pettinari, G.; Tedeschi, D.; Miriametro, A.; et al. Evidence of the direct-to-indirect band gap transition in strained two-dimensional WS<sub>2</sub>, MoS<sub>2</sub>, and WSe<sub>2</sub>. *Physical Review Research* **2020**, *2*, 2.
- (15) Zhu, Z. Y.; Cheng, Y. C.; Schwingenschlögl, U. Giant spin-orbit-induced spin splitting in two-dimensional transition-metal dichalcogenide semiconductors. *Phys. Rev. B* **2011**, *84*, 84.
- (16) Yu, H.; Cui, X.; Xu, X.; Yao, W. Valley excitons in two-dimensional semiconductors. *National Science Review* **2015**, *2*, 57–70.
- (17) Yuan, L.; Huang, L. Exciton dynamics and annihilation in WS<sub>2</sub> 2D semiconductors. *Nanoscale* **2015**, *7*, 7402–7408.
- (18) Tanoh, A. O. A.; Alexander-Webber, J.; Xiao, J.; Delpont, G.; Williams, C. A.; Bretscher, H.; et al. Enhancing Photoluminescence and Mobilities in WS<sub>2</sub> Monolayers with Oleic Acid Ligands. *Nano Lett.* **2019**, *19*, 6299–6307.
- (19) Seo, S.; Yang, D. R.; Moon, G.; Okello, O. F. N.; Park, M. Y.; Lee, S.; et al. Identification of Point Defects in Atomically Thin Transition-Metal Dichalcogenide Semiconductors as Active Dopants. *Nano Lett.* **2021**, *21*, 3341–3354.
- (20) Lin, Y. C.; Li, S.; Komsa, H. P.; Chang, L. J.; Krashennnikov, A. V.; Eda, G.; et al. Revealing the Atomic Defects of WS<sub>2</sub> Governing Its Distinct Optical Emissions. *Adv. Funct. Mater.* **2018**, *28*, No. 1704210.
- (21) Bianchi, M. G.; Risplendi, F.; Fiorentin, M. R.; Cicero, G. Engineering the Electrical and Optical Properties of WS<sub>2</sub> Monolayers via Defect Control. *Adv. Sci.* **2024**, *11*, No. 2305162.
- (22) Liu, B.; Chen, Y.; Ma, C.; Jiang, Y.; Zhang, D.; Xu, Z.; et al. Gallium doping-assisted giant photoluminescence enhancement of monolayer MoS<sub>2</sub> grown by chemical vapor deposition. *Appl. Phys. Lett.* **2022**, *120*, 120.
- (23) Xin, X.; Song, Y.; Guo, S.; Zhang, Y.; Wang, B.; Wang, Y.; et al. One-step synthesis of P-doped MoS<sub>2</sub> for efficient photocatalytic hydrogen production. *J. Alloys Compd.* **2020**, *829*, No. 154635.
- (24) Zhang, F.; Lu, Y.; Schulman, D. S.; Zhang, T.; Fujisawa, K.; Lin, Z.; et al. Carbon doping of WS<sub>2</sub> monolayers: Bandgap reduction and p-type doping transport. *Science. Advances* **2019**, *5*, No. eaav5003.
- (25) Chua, X. J.; Luxa, J.; Eng, A. Y. S.; Tan, S. M.; Sofer, Z.; Pumera, M. Negative Electrocatalytic Effects of p-Doping Niobium and Tantalum on MoS<sub>2</sub> and WS<sub>2</sub> for the Hydrogen Evolution Reaction and Oxygen Reduction Reaction. *ACS Catal.* **2016**, *6*, 5724–5734.
- (26) Stand, N.; Barbosa, A. N.; de Oliveira, P. R. A.; Mendoza, C. D.; Freire, F. L. Niobium doping of CVD-WS<sub>2</sub> monolayers using solid precursors with and without salt-KBr as a catalyst: A comparative study. *Appl. Surf. Sci.* **2024**, *657*, No. 159816.
- (27) Barbosa, A. d. N.; Mendoza, C. A. D.; Figueroa, N. J. S.; Terrones, M.; Freire, F. L. Luminescence enhancement and Raman characterization of defects in WS<sub>2</sub> monolayers treated with low-power N<sub>2</sub> plasma. *Appl. Surf. Sci.* **2021**, *535*, No. 147685.
- (28) Kumar, R.; Shringi, A. K.; Wood, H. J.; Asuo, I. M.; Oturak, S.; Sanchez, D. E.; et al. Substitutional doping of 2D transition metal dichalcogenides for device applications: Current status, challenges and prospects. *Materials Science and Engineering: R: Reports* **2025**, *163*, No. 100946.
- (29) Xu, X.; Guo, T.; Kim, H.; Hota, M. K.; Alsaadi, R. S.; Lanza, M.; et al. Growth of 2D Materials at the Wafer Scale. *Adv. Mater.* **2022**, *34*, 34.
- (30) Xia, Y.; Chen, X.; Wei, J.; Wang, S.; Chen, S.; Wu, S.; et al. 12-in. growth of uniform MoS<sub>2</sub> monolayer for integrated circuit manufacture. *Nat. Mater.* **2023**, *22*, 1324–1331.
- (31) Zeng, H.; Wen, Y.; Yin, L.; Cheng, R.; Wang, H.; Liu, C.; et al. Recent developments in CVD growth and applications of 2D transition metal dichalcogenides. *Frontiers of Physics in China* **2023**, *18*, 18.
- (32) Yang, H.-J.; Wang, Y.; Zou, X.; Bai, R.; Han, S.; Wu, Z.; et al. Growth Mechanisms and Morphology Engineering of Atomic Layer-Deposited WS<sub>2</sub>. *ACS Appl. Mater. Interfaces* **2021**, *13*, 43115–43122.
- (33) Coleman, E.; Monaghan, S.; Gity, F.; Mirabelli, G.; Duffy, R.; Sheehan, B.; et al. Scrutinizing pre- and post-device fabrication properties of atomic layer deposition WS<sub>2</sub> thin films. *Appl. Phys. Lett.* **2023**, *123*, No. 011901.
- (34) Wang, R.; Koch, N.; Martin, J.; Sadofev, S. Recrystallization of MBE-Grown MoS<sub>2</sub> Monolayers Induced by Annealing in a Chemical Vapor Deposition Furnace. *Phys. Status Solidi RRL* **2023**, *17*, No. 2200476.
- (35) Choi, S. H.; Yang, S.-H.; Park, S.; Cho, B. W.; Nguyen, T. D.; Kim, J. H.; et al. Is chemical vapor deposition of monolayer WSe<sub>2</sub> comparable to other synthetic routes? *APL Materials* **2023**, *11*, 11.
- (36) Stand, N.; Mendoza, C. D.; Freire, F. L. Synthesis of WS<sub>2</sub> by Chemical Vapor Deposition: Role of the Alumina Crucible. *Crystals* **2022**, *12*, 835.
- (37) Kresse, G.; Furthmüller, J. Efficient iterative schemes for ab initio total-energy calculations using a plane-wave basis set. *Phys. Rev. B* **1996**, *54*, 11169–11186.
- (38) Tkatchenko, A.; Scheffler, M. Accurate Molecular Van Der Waals Interactions from Ground-State Electron Density and Free-Atom Reference Data. *Phys. Rev. Lett.* **2009**, *102*, 102.
- (39) Kieczka, D.; Durrant, T. R.; Milton, K.; Goh, J.; Bosman, M.; Shluger, A. L. Defects in WS<sub>2</sub> monolayer calculated with a nonlocal functional: any difference from GGA? *Electron. Struct.* **2023**, *5*, No. 024001.
- (40) Zhang, Y.; Shi, J.; Han, G.; Li, M.; Ji, Q.; Ma, D.; et al. Chemical vapor deposition of monolayer WS<sub>2</sub> nanosheets on Au foils toward direct application in hydrogen evolution. *Nano Research* **2015**, *8*, 2881–2890.
- (41) Cong, C.; Shang, J.; Wang, Y.; Yu, T. Optical Properties of 2D Semiconductor WS<sub>2</sub>. *Advanced Optical Materials* **2018**, *6*, No. 1700767.
- (42) Cunningham, P. D.; McCreary, K. M.; Jonker, B. T. Auger Recombination in Chemical Vapor Deposition-Grown Monolayer WS<sub>2</sub>. *J. Phys. Chem. Lett.* **2016**, *7*, 5242–5246.
- (43) Carmiggelt, J. J.; Borst, M.; van der Sar, T. Exciton-to-trion conversion as a control mechanism for valley polarization in room-temperature monolayer WS<sub>2</sub>. *Sci. Rep.* **2020**, *10*, 10.
- (44) Zhao, H.; Zhang, G.; Yan, B.; Ning, B.; Wang, C.; Zhao, Y.; et al. Substantially Enhanced Properties of 2D WS<sub>2</sub> by High Concentration of Erbium Doping against Tungsten Vacancy Formation. *Research* **2022**, *2022*, 2022.
- (45) Jin, Y.; Zeng, Z.; Xu, Z.; Lin, Y.-C.; Bi, K.; Shao, G.; et al. Synthesis and Transport Properties of Degenerate P-Type Nb-Doped WS<sub>2</sub> Monolayers. *Chem. Mater.* **2019**, *31*, 3534–3541.
- (46) Iqbal, M. W.; Shahzad, K.; Akbar, R.; Hussain, G. A review on Raman finger prints of doping and strain effect in TMDCs. *Microelectron. Eng.* **2020**, *219*, No. 111152.
- (47) Kolesnichenko, P. V.; Zhang, Q.; Yun, T.; Zheng, C.; Fuhrer, M. S.; Davis, J. A. Disentangling the effects of doping, strain and disorder in monolayer WS<sub>2</sub> by optical spectroscopy. *2D Materials* **2020**, *7*, No. 025008.
- (48) Li, J.; Su, W.; Chen, F.; Fu, L.; Ding, S.; Song, K.; et al. Atypical Defect-Mediated Photoluminescence and Resonance Raman Spectroscopy of Monolayer WS<sub>2</sub>. *J. Phys. Chem. C* **2019**, *123*, 3900–3907.

(49) del Corro, E.; Botello-Méndez, A.; Gillet, Y.; Elias, A. L.; Terrones, H.; Feng, S.; et al. Atypical Exciton–Phonon Interactions in WS<sub>2</sub> and WSe<sub>2</sub> Monolayers Revealed by Resonance Raman Spectroscopy. *Nano Lett.* **2016**, *16*, 2363–2368.

(50) Barbosa, A.; Mendoza, C. A. D.; Lei, Y.; Giarola, M.; Terrones, M.; Mariotto, G.; et al. Photoluminescence quenching of CVD grown WS<sub>2</sub> monolayers treated with low-power Ar plasma. *Surf. Interfaces* **2022**, *33*, No. 102220.

(51) Wagner, C. *NIST X-Ray Photoelectron Spectroscopy (Xps) Database. Version 2*; MD: National Institute of Standards and Technology: Gaithersburg, 1997.

(52) Bourque, J. L.; Biesinger, M. C.; Baines, K. M. Chemical state determination of molecular gallium compounds using XPS. *Dalton Transactions* **2016**, *45*, 7678–7696.

(53) Ghosh, S. C.; Biesinger, M. C.; LaPierre, R. R.; Kruse, P. X-ray photoelectron spectroscopic study of the formation of catalytic gold nanoparticles on ultraviolet-ozone oxidized GaAs(100) substrates. *J. Appl. Phys.* **2007**, *101*, 101.

(54) Liu, Z.; Höfft, O.; Endres, F. Disproportionation Reaction of Gallium during Electrodeposition from an Ionic Liquid, Monitored by In Situ Electrochemical XPS. *J. Phys. Chem. C* **2021**, *125*, 24589–24595.

(55) Bader, R. F. *Atoms in molecules: a quantum theory*. Clarendon Pr: Oxford, 1990.

(56) Tang, W.; Sanville, E.; Henkelman, G. A grid-based Bader analysis algorithm without lattice bias. *J. Phys.: Condens. Matter* **2009**, *21*, No. 084204.

(57) Christopoulos, S.-R. G.; Kuganathan, N.; Chroneos, A. Electronegativity and doping in Si<sub>1-x</sub>Gex alloys. *Sci. Rep.* **2020**, *10*, 7459.



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